

FORM PTO 1449 (modified) U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE LIST OF REFERENCES CITED BY APPLICANT(S) (Use several sheets if necessary) Submitted to the PTO: November 30, 2007				ATTY DOCKET NO. 03500.017774		APPLICATION NO. 10/535,452	
				APPLICANTS MIKI OGAWA, ET AL.			
				FILING DATE May 19, 2005		GROUP 1765	
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*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
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/DD/		5,240,558	08/1993	Kawasaki, et al.	156	659.1	
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		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES/NO/ OR ABSTRACT
/DD/		5-55545	03/1993	Japan			Abstract
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/DD/		11-31862	02/1999	Japan			Abstract
/DD/		11-251334	09/1999	Japan			Abstract
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/DD/		M. Jacobs, et al., "Unbalanced Magnetron Sputtered Si-Al Coatings: Plasma Conditions and Film Properties Versus Sample Bias Voltage", Surface and Coatings Technology, 116-119, pp. 735-741 (1999).					
/DD/		C.D. Adams, et al., "Transition from Lateral to Transverse Phase Separation During Film Co-Deposition", Appl. Phys. Lett., 59 (20), pp. 2535-2537 (November 11, 1991).					
/DD/		M. Atzmon, et al., "Phase Separation During Film Growth", J. Appl. Phys. 72 (2), pp. 442-446 (July 15, 1992).					
EXAMINER				DATE CONSIDERED			
/Duy Vu Deo/ (02/19/2008)							

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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/DD/		2001-261376	09/2001	Japan			Abstract
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/DD/		WO 01/71394	09/2001	PCT			No
/DD/		2000-327491	11/2000	Japan			Abstract
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/DD/		C.D. Adams, et al., "Monte Carlo Simulation of Phase Separation During Thin-Film Codeposition", J. Appl. Phys., 74 (3), pp. 1707-1715 (August 1, 1993).					
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